

L Number	Hits	Search Text	DB	Time stamp
1	32346	205/\$ ccls.	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:31
2	0	nanobarcode	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:31
3	583	nanoparticle	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:31
4	57989	template	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:31
5	78723	colloidal	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:31
6	36318	photolithography	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:32
7	0	achromatic adj interference adj lithography	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:33
8	39	interference adj lithography	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:33
9	25	electrolytic same deposit\$3	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:34
10	7512	electrochemical same deposit\$3	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:34
11	583	nanobarcode nanoparticle	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:34
12	1360180	template substrate	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:35
13	2066	nanoparticle\$	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:35
14	2066	(nanobarcode nanoparticle) nanoparticle\$	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:35
15	700	(template substrate) and ((nanobarcode nanoparticle) nanoparticle\$)	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:35
16	4	((template substrate) and ((nanobarcode nanoparticle) nanoparticle\$)) and 205/\$.ccls.	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:36
17	36345	photolithography (achromatic adj interference adj lithography)	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:37
18	25	(photolithography (achromatic adj interference adj lithography) (interference adj lithography)) and ((template substrate) and ((nanobarcode nanoparticle) nanoparticle\$))	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:38
19	7537	(electrolytic same deposit\$3) (electrochemical same deposit\$3)	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:38
20	2	((photolithography (achromatic adj interference adj lithography) (interference adj lithography)) and ((template substrate) and ((nanobarcode nanoparticle) nanoparticle\$)) and (electrolytic same deposit\$3) (electrochemical same deposit\$3))	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:38
22	11936	Heller	USPAT; EPC; JPO; DEFWENT	2002/01/27 17:39

23	145	Southern.inv.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:39
24	1617	Heller.inv.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:39
25	1762	Southern.inv. Heller.inv.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:39
26	0	(Southern.inv. Heller.inv.) and ((electrolytic same deposit\$3) (electrochemical same deposit\$3)) and template	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:39
27	9	(Southern.inv. Heller.inv.) and ((electrolytic same deposit\$3) (electrochemical same deposit\$3))	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:40
28	18	Heller.inv. and 205/\$.ccls.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:41
29	1	Southern.inv. and 205/\$.ccls.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:42
30	77	Heller and 205/\$.ccls.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:49
31	2	("5929208").PN.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:43
32	2	("6093302").PN.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:51
33	3	("5667667").PN.	USPAT; EPO; JPO; DEPWENT	2002/01/27 17:51